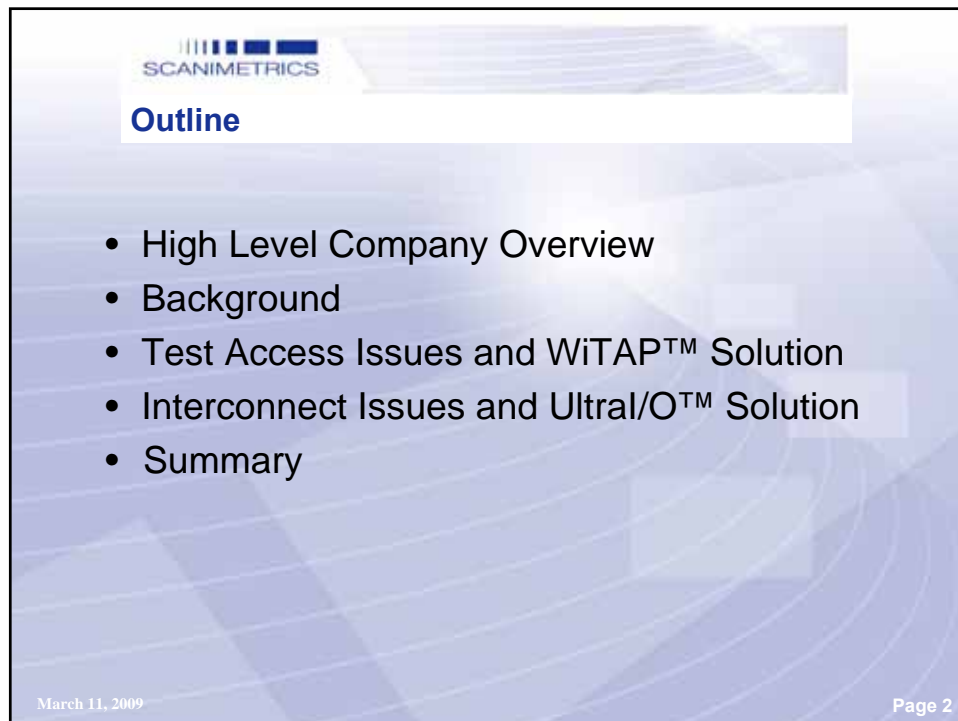




SCANIMETRICS
Semiconductor Technology Driving Change

**Non-Contact Wafer Testing and
High Performance, Low Power I/O
Chip-to-chip Communications**

March 11, 2009
Santa Clara Valley Chapter,
CPMT Society, IEEE




SCANIMETRICS

Outline

- High Level Company Overview
- Background
- Test Access Issues and WiTAP™ Solution
- Interconnect Issues and Ultra/O™ Solution
- Summary

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The Company

Scanimetrix provides solutions to bottlenecks imposed by traditional semiconductor I/O circuits

Our solutions address:

- Test access during fabrication and packaging of integrated circuits
- Speed and power consumption of integrated circuits

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The Value Chain

Scanimetrix can benefit the entire product chain

Design	Front End Process					Back End Process		
<ul style="list-style-type: none"> • Reduce chip size • Higher freq I/O • Lower power 	<ul style="list-style-type: none"> • No particles • In-line, real time 					<ul style="list-style-type: none"> • No particles • High Speed • High throughput • Lower test cost 		
Design	Deposition	Lithography	Etch	Inspection	Wafer Test	Dice	Package	Final Test

“(Scanimetrix) technology is seminal in nature and the impact will be profound.” - Denny Sabo, former CEO, Arithmos

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Current Wafer Probing Problems

- Contact Probes
 - Pitch, tip size, restricted pad size
- Pad Damage
 - Maximum allowable damaged area
- ESD Structures

How : Non-contact Test Access

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I/O Issues – Pad Pitch and ESD

2006 ITRS for Test

I/O Pad Min. Dimension (μm)	Year of Production								
	2005	2006	2007	2008	2009	2010	2011	2012	2013
Wirebond	35	30	30	25	25	25	25	20	20
Bump	75	75	60	60	50	50	50	50	50

- Bond / probe pads are not shrinking with circuit dimensions according to Moore's Law
- Probes: Pitches not shrinking, tip sizes not changing
- Pad Damage: Maximum allowable damaged area is decreasing
- ESD structures affect signal speed and power consumption

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Packaging is Critical

***Packaging is now a limiting factor;
But is an enabler for more than Moore***

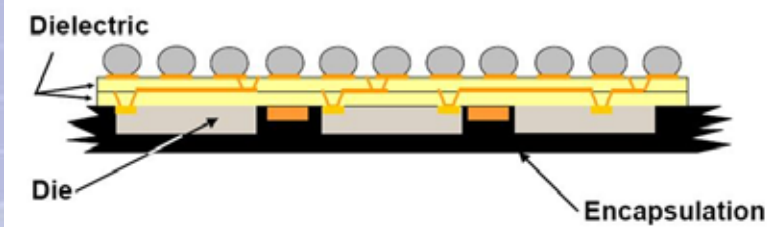
- Packaging has become the limiting element in system cost and performance
- The assembly and packaging role is expanding to include system level integration functions
- As traditional Moore's Law scaling becomes more difficult innovation in assembly and packaging can take up the slack

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I/O Issues – Testability of New Technologies

- Redistributed Chip Packaging (RCP)
 - Die connections are redistributed and brought to the outside as part of the package build
 - No pads needed on the die, so how do you test?



From : B. Keser
Freescale Semiconductor
2007 Freescale Technology Forum

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SiP Challenges

- Assembly yields low
 - Yield is product of die yields
 - Testability during assembly is non-existent
 - Probing SiP modules difficult due to
 - Mechanical issues
 - Varying component heights
 - Good die lost during substrate build-up process
- Design kits for SiP not available from Vendors
- Vendor availability for start-up volumes
 - Lack of low-volume manufacturing capacity

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I/O Issues - Data rate roadmap

ITRS Roadmap

- 10 Gbps I/O available
- Power >8 mW/Gbps
- Tbps data rates
- Communications
- Data storage
- Image processing

Year	Data Rate (Gbps)
2007	10
2008	20
2009	40
2010	80
2011	160

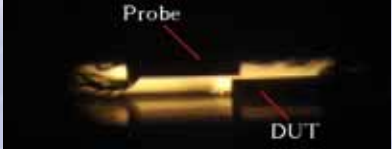
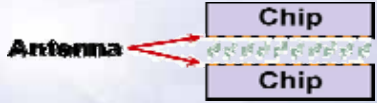
A good measure (Figure of Merit) is Speed times Distance per unit of Power

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The Technology

- Inductive chip-scale communications
- Micro Tx/Rx on chip
- One Tx/Rx per I/O
- High speed
- Low power
- Pitch scales to <20um





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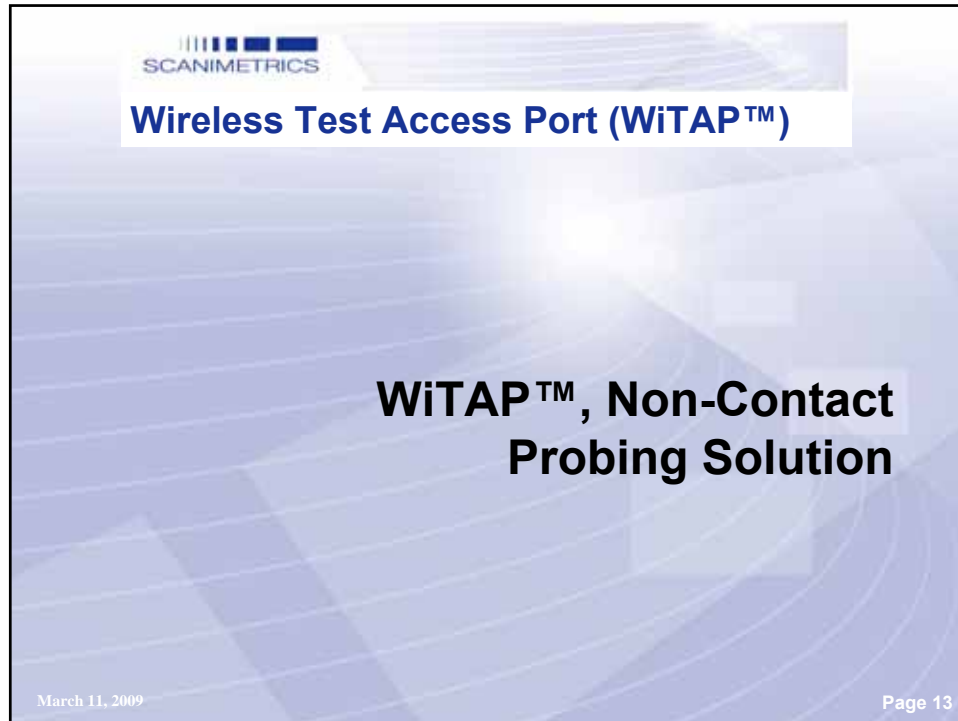
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The Products

- **Ultra/I/O™**
 - Semiconductor I/O circuit IP
 - FASTER data rates
 - LOWER power consumption
 - SMALLER size
- **WiTAP™ product family**
 - Semiconductor test access IP and probe card
 - Advanced package testing
 - Wafer probing



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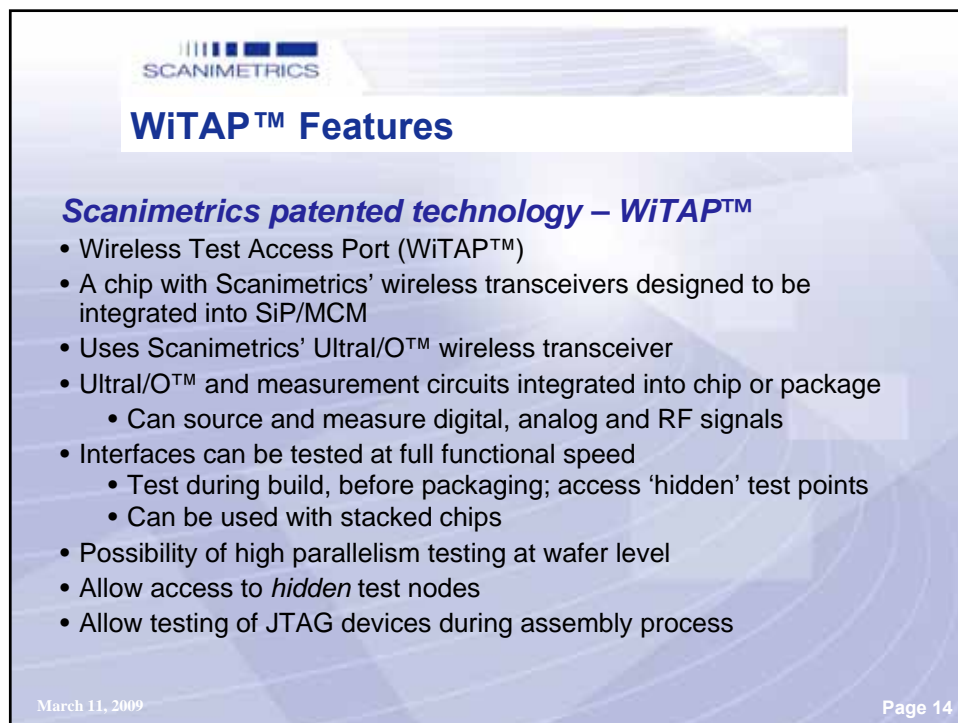


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Wireless Test Access Port (WiTAP™)

WiTAP™, Non-Contact Probing Solution

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WiTAP™ Features

Scanimetrics patented technology – WiTAP™

- Wireless Test Access Port (WiTAP™)
- A chip with Scanimetrics' wireless transceivers designed to be integrated into SiP/MCM
- Uses Scanimetrics' Ultra/O™ wireless transceiver
- Ultra/O™ and measurement circuits integrated into chip or package
 - Can source and measure digital, analog and RF signals
- Interfaces can be tested at full functional speed
 - Test during build, before packaging; access 'hidden' test points
 - Can be used with stacked chips
- Possibility of high parallelism testing at wafer level
- Allow access to *hidden* test nodes
- Allow testing of JTAG devices during assembly process

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WiTAP™ Features

Wafer test

Probe Chip Mount

Standard Probe Card PCB

Power Connections Probes

Wafer to be Tested

SiP test

Probe Chip Mount

Standard Probe Card PCB

Power Connections Probes

SiP Substrate

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WiTAP™ Features

Probe Chip

WiTAP™ I/O Cell

Contact Pad

DUT


WiTAP™ I/O Cell

Probe Tip

Matching Antenna Pattern on Wireless Probe Card


Single DUT Die with Standard I/O Cells Replaced with Wireless I/O Cells

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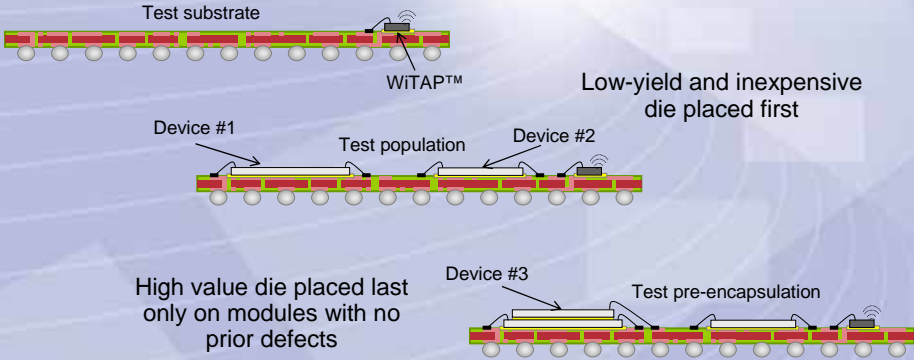

WiTAP™ SiP Testing Solution

- **Complex SiP designs presently are not cost-effective**
 - Overall yield is product of individual die yields and assembly yield
 - Mechanical issues and contact probing restrictions prevent testing during assembly process
- **Solution: Scanimetrics' Wireless Test Access Port (WiTAP™)**
 - Enables design of complex SiP devices with high manufacturing yields
 - Lessens known good die (KGD) requirements of individual die
 - Allows testing of the SiP like a wafer during the assembly process
 - *On a prober, with a probe card*
 - WiTAP™ enables cost-effective SiP assembly and manufacturing

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WiTAP™ SiP Testing Solution

Can be implemented as an independent chip populated on the SiP substrate or as an IP block embedded in other chips



Test substrate

WiTAP™

Low-yield and inexpensive die placed first

Device #1

Test population

Device #2

High value die placed last only on modules with no prior defects

Device #3

Test pre-encapsulation

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WiTAP™ SiP Testing Solution

WiTAP™ non-contact probing solution

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WiTAP™ SiP Testing Solution

Features	Benefits
<p>Monitor quality of SiP process in real-time</p>	<ul style="list-style-type: none"> • Detect problems earlier in the process • Early detection yield excursions • Reduce number of dies wasted • Reduce assembly cost up to 30% or more

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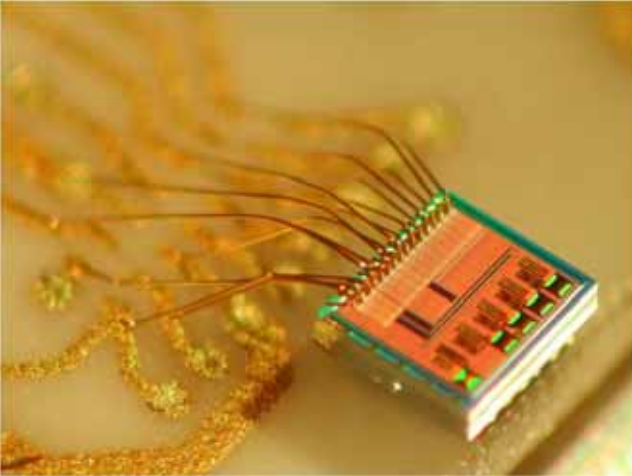
WiTAP™ SiP Testing Solution

Features	Benefits
Non-contact signal probing at high speeds	<ul style="list-style-type: none">• Less probing debris• Less damage to circuits and pads• Less damage to probe cards• More robust process• Full speed testing at wafer level

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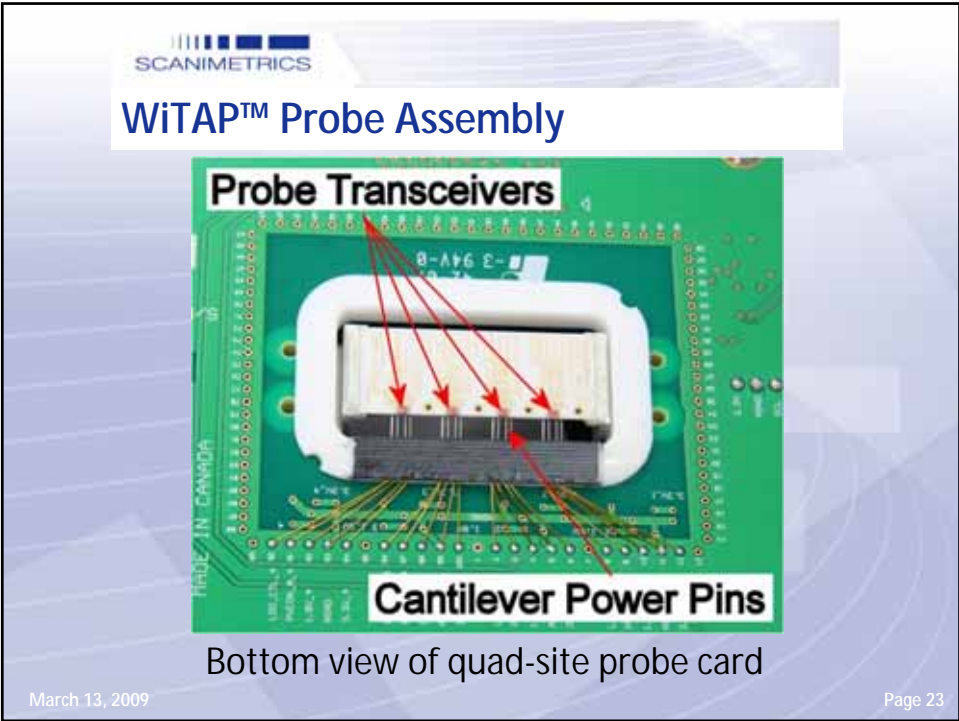
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WiTAP™ Probe



Single WiTAP™ chip

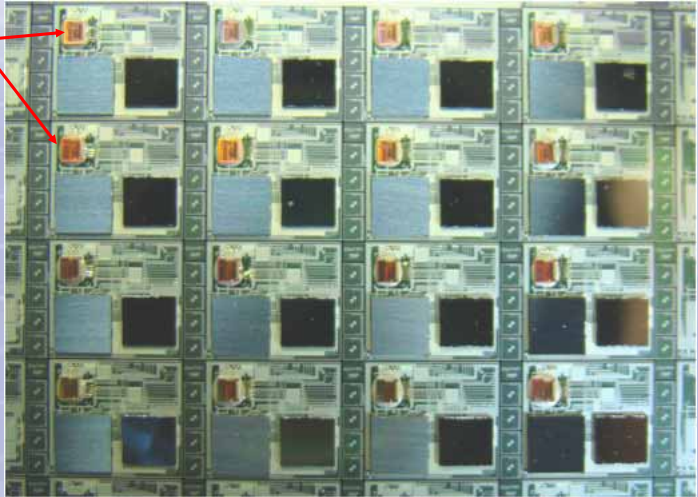
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WiTAP™ SiP DUT

WiTAP™ on SiP module for customer application



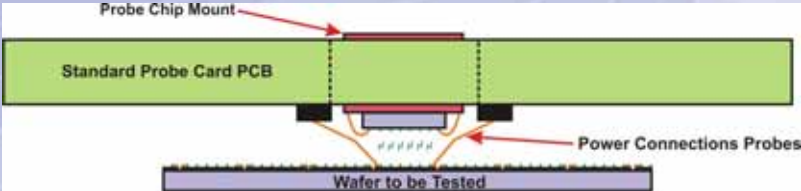
March 13, 2009

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Wafer Probe Application

- Interfaces can be tested at full functional speed at the wafer level (SerDes, DDR2, DDR3)
- Supports internal test points with no ESD protection requirements
- Possibility of high parallelism testing at wafer level



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Wafer Probe Solution

Features	Benefits
<p>Non-contact signal probing at high speeds</p>	<ul style="list-style-type: none"> • Less probing debris • Less damage to circuits and pads • Less damage to probe cards • Less I/O pads and routing area • More robust process

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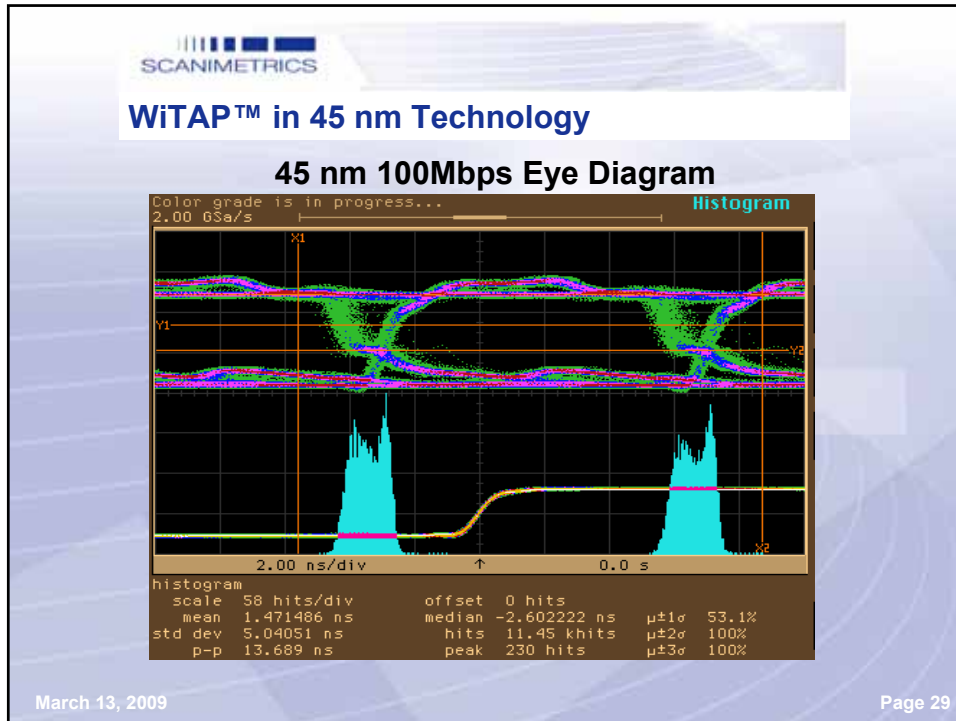
WiTAP™ Product

Alignment Tolerance

- Wide alignment tolerance
- 120 μm antennas
- Envelope of <math><10^{-13}</math> error rate

Lateral Distance (um)	Sim (um)	Meas. (um)
0	125	110
20	120	105
40	105	90
60	90	60
80	10	10

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- WiTAP™ SiP product qualified for production by top 10 semiconductor firm Q308 in 130 nm
- Non-contact test circuits migrated to 45 nm and demonstrated in Q208
 - Faster and lower power

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Ultra/O™

Ultra/O™, High Performance Low Power Chip-to-chip interconnect

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Ultra/O™ - Background

"The growing number of full-featured, media-rich mobile applications is creating an increased demand for more memory.

Serial Port Memory Technology will be the right solution to support the requirements for **low pin count**, **low power** and **high bandwidth** that will be required for these new applications."

*JB Kim, senior vice president of technical marketing,
Hynix, member of SPMT group*

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I/O Issues - Data rate roadmap

**Chip power density greater than a
'Formula One' engine
>1.5 kW/cu.in ... and increasing!**

- Current technology is out of Gas!!!!
- I/O performance measured by speed, power, distance, density (size)
- I/O complexity is increasing
- Speed is available at expense of power
- I/O is not scaling with technology nodes
- Chips are pad and power limited
- Power at Gigabit rates needs to fall
- Testability issues


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The Options – Wired or Wireless

- Wireline I/O (Rambus)
 - Requires complex on-chip clocking with related jitter sensitivity issues (clocking overhead power of 3.6 mW for 6.25 Gbps link)
 - Requires complex equalization circuitry with related jitter sensitivity issues (8mW for 6.25 Gb/s link)
 - Problems with ESD protection structures loading Rx inputs
 - Requires complex pre-emphasis circuitry with related jitter sensitivity issues (4.9 mW for 6.25 Gbps link)
 - Problems with ESD protection structures and PCB parasitics loading Tx outputs


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The Options – Wired or Wireless

- Optical
 - Does not have many of the limitations present in electrical signals. However, to enter the optical domain electrical signals have to be converted using optical transceivers
 - These circuits dissipate almost as much power as transceivers that drive PCBs and short backplanes
 - Only useful alternative is to have signal processed and transmitted entirely in optical domain. However, there are many performance problems with silicon photonics
 - Even if performance problems are solved it is doubtful that fully optical links will be economical over short distances
 - Silicon having an indirect bandgap provides no easy path to the integration of optics especially with regard to photon generation

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Other approaches to I/O connectivity

Why NOT other types of interconnections?

- **Capacitive** requires very close chip spacing => not practical
- **Inductive** extends range => but not far enough still not practical
- Research stage coupling solutions (Sun/ST/Kuroda) offers Tbps rates => but only up to 100 μ m distance
- Traditional I/O, Flex I/O, SerDes => require large power and area

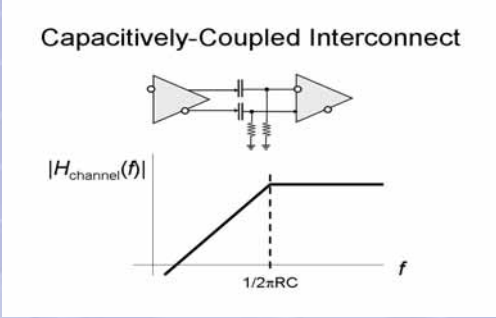
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Capacitively-coupled Interconnect

- Limited bandwidth on low frequency side (requires high coupling capacitance)
- Receive equalization helps that burns more power
- On-chip coupling capacitor requires very close spacing between capacitor plates

Capacitively-Coupled Interconnect

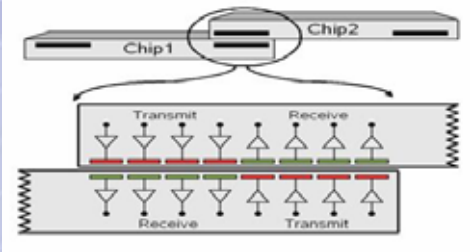



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Capacitive Coupling I/O

- Proximity chip to chip communications
 - Non-contact, very high speed chip-to-chip communications programs in development for I/O
- No probe/bond pads required, so what is the testing solution?



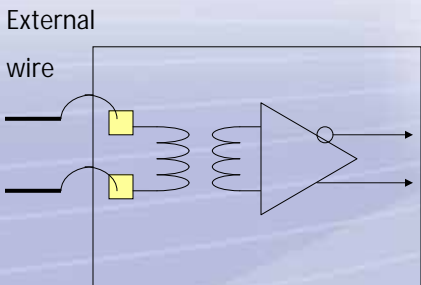
From : A. Fazzi: et.al.
ST Microsystems
2007 ISSCC

From : D. Hopkins: et al
Sun Microsystems
2007 ISSCC

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Inductive Coupling I/O



External wire

Low power
Data rates are 2.5Gbps now
Major target is 10 Gbps

- High Speed
- Signal Integrity
- Small Size
- Less ESD

- Uses the fact that transformer has inductance to overcome input capacitance.

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Scanimetrix Inductive Coupling Solution – UltraI/O™

- **High speed:** >20 Gbps per channel -> 1 Tbps chip-to-chip
- **Low power:** < 1 mW per Gbps
- **Small circuit size:** < 250 μm^2 at 45 nm
- **Scalable**

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Scanimetrics Inductive Coupling Solution – Ultra I/O™

- Less ESD protection is required since no DC connection
- Power, speed, distance and size much better than capacitive coupling and wireline solutions
- 3D packaging compatible
- Scanimetrics wireless test solution: WiTAP™ (Wireless Test Access Port) can be used to verify Ultra I/O™ connections

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Scanimetrics Inductive Coupling Solution – Ultra I/O™

Ultra I/O™ enables interconnection of die on SiP device


- A large single die replaced with a SiP consisting of many smaller die
- Smaller die can be interconnected using Ultra I/O™ at data rates equivalent to those on a single die with low power consumption
- Very cost-effective (more than 5X) for FPGA applications

The diagram illustrates the transition from a single large chip to a SiP device. On the left, a single 2 cm x 2 cm chip is shown with internal high-speed buses. An arrow points to the right, where four 1 cm x 1 cm chips are arranged in a 2x2 grid. Each chip is connected to its neighbors via Scanimetrics Ultra I/O™ buses, forming a mesh network. The text 'Scanimetrics Ultra I/O™ high speed chip-to-chip communication' is placed near the interconnections.

Before:
2 cm x 2 cm chip with internal high-speed buses connecting on-chip circuits

After:
Multiple, smaller chips providing same functionality, interconnected with high speed Scanimetrics Ultra I/O™ buses


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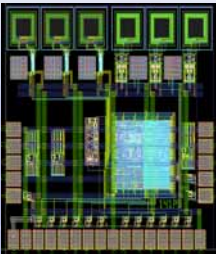
Ultra/O™ features and benefits

Feature	Benefit
<p>Higher Bandwidth Higher performance designs Fewer I/Os</p>	<p>New Applications Smaller Chips Less pin counts Less expensive packages</p>
<p>Lower power consumption Simpler package Less Heat</p>	<p>Cheaper packages Simpler system level designs</p>
<p>Smaller Size Less area Scalable</p>	<p>Lower cost Future Proof</p>
<p>Simpler Signaling schemes Easier circuit design Simpler board/package designs</p>	<p>Faster cycle time Lower cost system design</p>

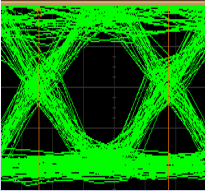
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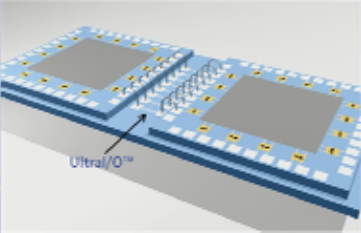
Ultra/O™ results at 130 nm



Gen 2 chip

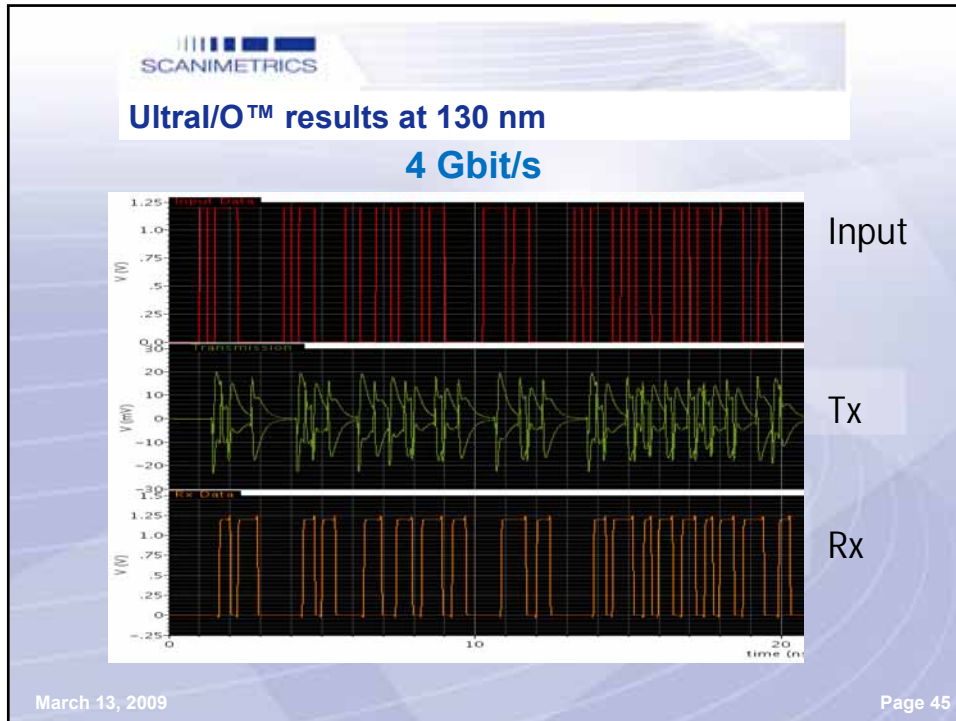



Eye diagram of PRBS at 475MBits/s



Ultra/O™

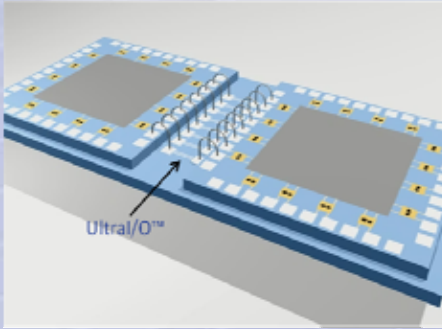
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Ultral/O™ Applications

Applications of Ultral/O™ includes but not limited to:

- Multiprocessor systems
- High performance multi device Network processing
- High performance Graphics
- High speed I/O bridging
- Multi-FPGA designs
- Raw camera imaging
- Cellular modem
- Compressed video




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Comparisons of Ultral/O™ to LPDDR2

	LPDDR2 Specifications	Implementation Using Ultral/O™
BOM cost	2 or more RAM	1 RAM
Signal pins	53 @ 800 Mbytes/sec 69 @ 3.2 Gbytes/sec	2 @ 800 Mbytes/sec 4 @ 3.3 Gbytes/sec
I/O power	60 mW @ 800 Mbytes/sec 220 mW @ 3.2 Gbytes/sec	7.2 mW @ 800 Mbytes/sec 30 mW @ 3.3 Gbytes/sec

• Higher Ultral/O™ bandwidth can be achieved by adding more signal channels


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Comparisons of Ultral/O™ to PCI Express

	PCI Express Gen 3 Specifications	Implementation Using Ultral/O™
Signal pins	2 @ 800 Mbytes/sec 8 @ 3.2 Gbytes/sec	2 @ 800 Mbytes/sec 4 @ 3.3 Gbytes/sec
I/O power	120 mW @ 800 Mbytes/sec 480 mW @ 3.2 Gbytes/sec	7.2 mW @ 800 Mbytes/sec 30 mW @ 3.3 Gbytes/sec

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Comparisons of Ultral/O™ to MIPI UniProSM

	MIPI UniPro Specifications	Implementation Using Ultral/O™
Signal pins	16 @ 800 Mbytes/sec 64 @ 3.2 Gbytes/sec	2 @ 800 Mbytes/sec 4 @ 3.3 Gbytes/sec
I/O power	28 mW @ 800 Mbytes/sec 112 mW @ 3.2 Gbytes/sec	7.2 mW @ 800 Mbytes/sec 30 mW @ 3.3 Gbytes/sec

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Overview

1 Testing DUT A

2 Testing DUT B

3 Testing SiP

4 Normal Operation


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Ultral/O™ Summary

- Current memory interface technology cannot meet growing demand of mobile handheld industry and other markets such as portable media player and digital cameras
- Ultral/O™ offers faster, lower power and smaller area solutions than other approaches such as capacitive and inductive interconnects
- Ultral/O™ has superior performance than current interface standards (LPDDR2, PCI Express, MIPI UniproSM)
- Ultral/O™ is an excellent candidate for the next chip-to-chip and memory interface standards

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Ultral/O™ - Summary

"The growing number of full-featured, media-rich mobile applications is creating an increased demand for more memory.

Serial Port Memory Technology will be the right solution to support the requirements for **low pin count**, **low power** and **high bandwidth** that will be required for these new applications."

*JB Kim, senior vice president of technical marketing,
Hynix, member of SPMT group*

Ultral/O™ fills this technology gap. □

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